

d his

(FILE 'HOME' ENTERED AT 14:53:54 ON 24 APR 2006)

FILE 'REGISTRY' ENTERED AT 14:54:05 ON 24 APR 2006

L1 STR
L2 21 S L1
L3 STR L1
L4 3 S L3
L5 27 S L3 FUL

FILE 'CAPLUS' ENTERED AT 15:06:49 ON 24 APR 2006

L6 35 S LS

FILE 'REGISTRY' ENTERED AT 15:07:09 ON 24 APR 2006

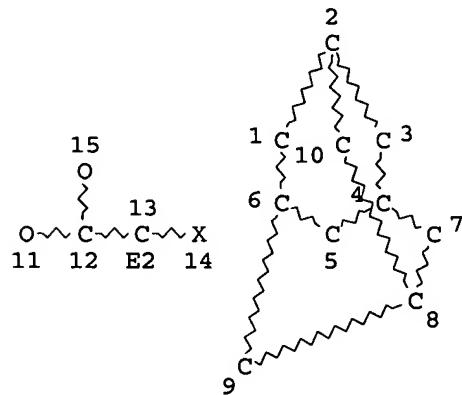
FILE 'CAPLUS' ENTERED AT 15:15:13 ON 24 APR 2006

FILE 'STNGUIDE' ENTERED AT 15:27:14 ON 24 APR 2006

FILE 'CAPLUS' ENTERED AT 15:33:21 ON 24 APR 2006

FILE 'STNGUIDE' ENTERED AT 15:33:21 ON 24 APR 2006

=> d 13 sia
L3 HAS NO ANSWERS
L3 STR



NODE ATTRIBUTES:

HCOUNT IS E2 AT 13
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

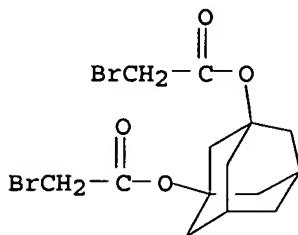
GRAPH ATTRIBUTES:

RSPEC I
NUMBER OF NODES IS 15

STEREO ATTRIBUTES: NONE

=>

ANSWER 9 OF 27 REGISTRY COPYRIGHT 2006 ACS on STN
RN 267423-13-2 REGISTRY
ED Entered STN: 31 May 2000
CN Acetic acid, bromo-, tricyclo[3.3.1.13,7]decane-1,3-diyl ester (9CI) (CA
INDEX NAME)
FS 3D CONCORD
MF C14 H18 Br2 O4
SR CA
LC STN Files: CA, CAPLUS



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

REFERENCE 1

AN 132:341187 CA
TI Contrast-boosted photoresist composition and fine patterning of the
photoresist
IN Namiki, Takahisa; Yano, Akira; Watabe, Keiji; Kon, Junichi
PA Fujitsu Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

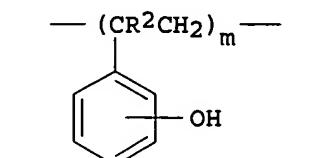
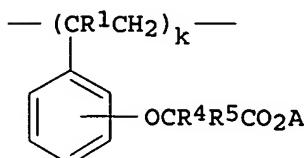
| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---------------------|------|----------|-----------------|----------|
| PI JP 2000131848 | A2 | 20000512 | JP 1999-142051 | 19990521 |
| PRAI JP 1998-236108 | | 19980821 | | |

AB The composition contains a polymer and a compound substituted with OCOCR1R2X
(X =
halogen; R1, R2 = H, alkyl, Ph) for boosting contrast. The composition containing
the polymer having side chain groups for reacting with acids to increase
alkaline developer solubility, an agent for releasing acids under ionizing
radiation, and the agent for boosting contrast is applied on a substrate
to form a photoresist film, which is partially exposed, heated, and
developed by an alkaline liquid to give the contrast-boosted pattern.

L6 ANSWER 25 OF 35 CAPLUS COPYRIGHT 2006 ACS on STN

1996:520454 Document No. 125:154399 Radiation-sensitive resist composition containing 1-adamantyl-substituted vinylphenol component. Matsuno, Shugo; Sugimoto, Tatsuya; Abe, Nobunori; Tanaka, Hideyuki (Nippon Zeon Co, Japan). Jpn. Kokai Tokkyo Koho JP 08137107 A2 19960531 Heisei, 7 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 1994-301558 19941110.

GI



I

II

AB The composition contains a copolymer having an adamantyl-substituted component I, a phenolic component II, and [CR₃(CO₂R₆)]_n [R₁₋₃ = H, (substituted) C₁₋₄ alkyl, halo, CN, NO₂, R₄, R₅ = H, (branched) C₁₋₈ (substituted) alkyl, (substituted) alkenyl, (substituted) aryl, A = 1-adamantyl, R₆ = acid-instable group; 0.05 ≤ k ≤ 0.95; 0.1 ≤ l ≤ 0.95; 0.05 ≤ n ≤ 0.6; k + m + n = 1] and a radiation-sensitive component which generates an acid by active radiation. The composition showing high sensitivity, resolution, and etching resistance is useful for super-fine processing in manufacture of semiconductor devices.

IT 180273-21-6DP, reaction products with hydroxy-containing acrylic polymers

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(radiation-sensitive resist composition containing 1-adamantyl-substituted vinylphenol component)

RN 180273-21-6 CAPLUS

CN Acetic acid, bromo-, tricyclo[3.3.1.13,7]dec-1-yl ester (9CI) (CA INDEX NAME)

